Amendments to the Specification:

The paragraph starting at page 1, line 20, is amended and now reads as follows:

-- United States Patent 6,822,729 ~~patent publication US-2001/0019404~~ is incorporated herein by reference and discloses a method for microlithographic image generation wherein microlithography with tangentially polarized illumination is explained in detail as is the preparation thereof. However, no suggestion is provided in this publication as to a connection to refraction characteristics of the lens material. Systems having radial polarization are also discussed in this publication. --

The paragraph starting at page 1, line 28, is amended and now reads as follows:

-- United States ~~patent application serial no. 09/451,505, filed November 30, 1999~~ Patent 6,683,729 (corresponding to German patent publication 199 29 701), is incorporated herein by reference and touches upon MgF_2 as a lens material for the DUV/VUV range. However, this material is deemed to be unsuitable because of the double refraction. --

The paragraph starting at page 3, line 14, is amended and now reads as follows:

-- United States ~~patent publication US-2001/0019404~~

Patent 6,822,729 discloses that the tangential or radial polarization, which is needed as a condition precedent for the use of double-refracting material, has advantages also for image contrast and can be made available in different ways. According to the invention, it is therefore provided that all lenses, which consist of optically single-axis double-refracting material, are aligned with the optical crystal axis parallel to the optical axis. --

The paragraph starting at page 7, line 7, is amended and now reads as follows:

-- A light beam, whose polarization is perpendicular to the ~~plane~~ plane, which plane is formed by the propagation direction and the crystal axis, is therefore a proper ray and experiences no double refraction when passing through the crystal. For such a ray, the optical medium has only a refractive index n_0. If one produces a lens made of double-refracting material so that its optical axis is coincident with the crystal axis, then one achieves a constant index of refraction for all tangential rays with this polarization and even independently of the position and angle of incidence of these rays on the lens. In this way, the imaging quality of the lithographic objective is not influenced by the double refraction of the lens, which is positioned in proximity to the objective pupil, for the tangential rays. --